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2	Supporting Information				
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4	Benzyipnosphonic Acid treated Ultra-thin ALD-InOx for				
5	Long term Device Stability				
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43 liquid (L), γ_{SV} is the SE the S-vapor (V), γ_{LV} is the SE. The SE L-V, and theta (θ) is the CA of

44 the test liquid on the solid surface.

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46 In general, for CA and SE, it has been useful to analyze between solid surfaces and other 47 materials such as films. So, this system provides a wealth of information that can be used to 48 interpret surface/interface properties. From this perspective, to investigate the SE, the CA 49 method was used to confirm the change from hydrophilic to hydrophobic on the surface of 50 untreated In_2O_3 film and BPA- In_2O_3 film. As shown schematically in Figure S1, the CA testing 51 method appears to be a simpler option when compared to other characterization methods such 52 as electrical and optical testing

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Table 1. Surface energy (SE) components of the test liquid with polar and dispersive SE

57	Test liquid	Tension (mJ/m ²)	Dispersive (mJ/m ²)	Polar (mJ/m ²)
58	Deionized water (DI)	72.8	22.5	50.3
59	Ethylene glycol (EG)	48.3	39.3	19

60

61 Table S1. The test liquid parameter values used here for polar and non-polar

62 liquids.

63

64 As shown the Table S1, the conventional testing liquid with different polar and dispersive

65 components is used for testing. The polar and dispersive SE components of the two test liquids

66 used in the study. To interpret the SE from the acquired CA data acquisition, it used to the

67 owens-wendt method (OW) equation method. The polar and non-polar testing liquids were

68 used the DI and EG, respectively. The OW models obtained information about the trend of SE

as the surface changes from hydrophilic to hydrophobic temporal for untreated In₂O₃ and BPA-

70 In₂O₃ films.



93 bottom image shows the XRD peak information of the In_2O_3 film.





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Fig. S4. This transfer curve shows the stability under thermal conditions at 60 °C. Positive and
negative bias temperature stress (NBTS and PBTS).

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Fig. S4 (a) shows the NBTS under 60 °C at $V_G \pm 5$ V up to 3,000 sec. For the O₂ anneal In₂O₃ 120 TFT, the V_{th} shifted further in the negative direction, from -3.62 V initially to -6 V after 3,000 121 sec. The O₂ anneal with BPA and BPA In₂O₃ TFTs exhibited V_{th} values of -2.1 V and -0.4 V, 122 respectively, after 3,000 sec. The stability of In₂O₃ TFT is due to the back-channel layer of the 123 ultra-thin In₂O₃ film, which acts as the interfacial channel between the semiconductor and the 124 insulator. This back channel is more dominant than the interfacial channel layer between the 125 semiconductor and insulator, resulting in stable device characteristics with surface 126 modification. The PBTS exhibits a similar trend to the NBTS measurement results. In the case 127 of O₂ annealed In₂O₃ TFT, the initial -3.3 V shifted significantly in the positive voltage 128 129 direction to -1.24 V after 3,000 sec. However, the O2 annealed In2O3 TFTs with BPA passivation showed a larger positive voltage shift from an initial -3.3 V to 2.2 V after 3,000 130 131 sec. The increase in electron carriers at the interface is due to the oxygen injected through O₂ annealed treatment inside the film, which results in more In-O bonds being broken and the 132 oxygen becoming more In-O. For the BPA-only In₂O₃ TFT, the V_{th} initially measures 0.35 V. 133 As the existing carrier concentration remains constant, it shifts approximately 0.65 V in the 134 positive direction. After 3,000 sec, the V_{th} value reaches 1 V, given that the initial V_{th} was 0.35 135 V and the existing carrier concentration remained constant. The results indicate that aromatic 136 rings with a chemically stable structure can maintain the V_{th} stability of In₂O₃ TFT even in 137 thermal environments. 138



Fig. S5. This graph illustrates the temporal dependency of field-effect mobility in In_2O_3 TFTs treated with O_2 anneal, O_2 anneal+BPA, and BPA. As the results, regardless of the treatment method and time intervals, In_2O_3 TFTs exhibit non-varying mobility of 41.1 cm² V⁻¹s⁻¹, 40.6 cm² V⁻¹s⁻¹, and 41.2 cm² V⁻¹s⁻¹ for the O_2 anneal only, O_2 anneal+BPA, and BPA only treatments, respectively.